

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Atty. Docket

KURT et al.

NL 021426

Serial No.

Group Art Unit

Filed: CONCURRENTLY

Ex.

USE OF BI-LAYER PHOTOLITHOGRAPHIC RESISTS AS NEW MATERIAL FOR
OPTICAL STORAGE

Commissioner for Patents
Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT

Sir:

Prior to calculation of the filing fee and examination, please
amend the above-identified application as follows: